

AMENDMENTS TO THE CLAIMS

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1. (Currently Amended): A method for manufacturing a semiconductor device comprising:
- forming a dummy gate electrode on a semiconductor substrate having a predetermined length coincident with a length of a gate electrode to be formed;
 - with the dummy gate electrode used as a mask, forming one pair of first impurity diffusion layers in regions of the semiconductor substrate which are opposite to each other on opposite sides of the dummy gate electrode;
 - forming an insulating film on the semiconductor substrate so as to bury the dummy gate electrode and exposing an upper surface of the dummy gate electrode;
 - removing the dummy gate electrode to form a first trench electrode in the insulating film having a width corresponding to at least the predetermined length of the dummy gate;
 - enlarging the width of the first trench on each side of the first trench by a predetermined amount to form a second trench in the insulating film without etching the semiconductor substrate, said predetermined amount being equal to or greater than a thickness of a gate insulation film to be lined on an inner surface of the second trench;
 - lining the gate insulating film of said thickness along the inner surface of the second trench; and
 - forming the gate electrode in the second trench with only the gate insulating film intervening therebetween.
2. (Previously Amended): The method according to claim 1, further comprising:

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after forming the first impurity diffusion layers, forming a side wall insulating film on a side wall surface of the dummy gate electrode; and

with the dummy gate electrode and the sidewall insulating film used as a mask, forming second impurity diffusion layers having a deeper junction in the semiconductor substrate than the first impurity diffusion layers.

3. (Previously Amended): The method according to claim 1, wherein the forming of a second trench includes performing an isotropic etching on the insulating film having the first trench formed therein.

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Claim 4. (Canceled).

5. (Previously Amended): The method according to claim 1, wherein the forming of the gate insulating film includes using an insulating material having a relative dielectric constant of above 5.

6. (Previously Amended): The method according to claim 1, wherein the forming of a gate insulating film includes using an insulating material selected from the group consisting of Ta₂O₅, silicon nitride, Al₂O₃, BaSrTiO₃, Zr oxide, Hf oxide, Sc oxide, Y oxide and Ti oxide.

7. (Currently Amended): A method of manufacturing a semiconductor device, comprising:

forming a first insulating film on a semiconductor substrate;
sequentially forming a first semiconductor film and a second insulating film on the first insulating film;
forming a resist pattern on the second insulating film;

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with the resist pattern used as a mask, patterning the first semiconductor film and the second insulating film by an anisotropic etching to provide a stacked layer structure of the first semiconductor film and the second insulating film on the semiconductor substrate having a predetermined width coincident with a length of a gate electrode to be formed;

with the stacked layer structure used as a mask, ion-implanting an impurity in the semiconductor substrate to provide first impurity diffusion layers for a source and a drain;

forming a third insulating film over the semiconductor structure to bury the stacked layer structure;

etching back the third insulating film to expose an upper surface of the stacked layer structure;

with the third insulating film used as a mask, removing the stacked layer structure to form a trench in the third insulating film;

after forming the trench, enlarging the width of the trench by an isotropic etching by a predetermined width amount on each side of the trench that is equal to or larger than a thickness of a fourth insulating film along an inner surface of the trench without etching the semiconductor substrate;

after enlarging the width of the trench, depositing the fourth insulating film of said thickness along the inner surface of the trench; and

forming a conductive layer on and in contact with the fourth insulating film to form said gate electrode of a length coincident with the predetermined width.

8. (Previously Amended): The method according to claim 7, further comprising:

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after providing the first impurity diffusion layers, forming a sidewall insulating film on a sidewall of the stacked layer structure; and

with the sidewall insulating film and the staked layer structure used as a mask, forming second impurity diffusion layers having a deeper junction in the semiconductor substrate than the first impurity diffusion layers.

9. (Previously Amended): The method according to claim 7, wherein the enlarging of the width of the trench includes using, as the isotropic etching, an etching treatment including HF or NH₄F.

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10. (Previously Amended): The method according to claim 7, wherein the depositing of the fourth insulating film includes depositing by a chemical vapor deposition method or a sputtering method.

Claim 11. (Canceled).

12. (Previously Amended): The method according to claim 7, wherein the depositing of the fourth insulating film includes using an insulating material having a dielectric constant of above 5.

13. (Previously Amended): The method according to claim 7, wherein the depositing of the fourth insulating film includes using an insulating material selected from the group consisting of Ta₂O₅, silicon nitride, Al₂O₃, BaSrTiO₃, Zr oxide, Hf oxide, Sc oxide, Y oxide and Ti oxide.

Claims 14-18 (Withdrawn).